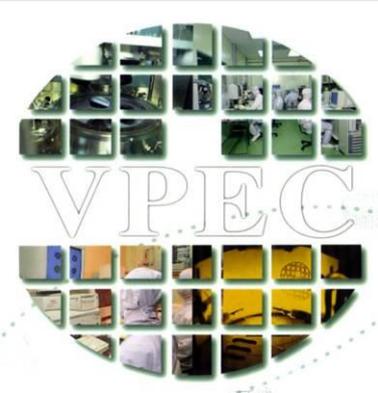




Company Profile

World-class leading edge with MOCVD

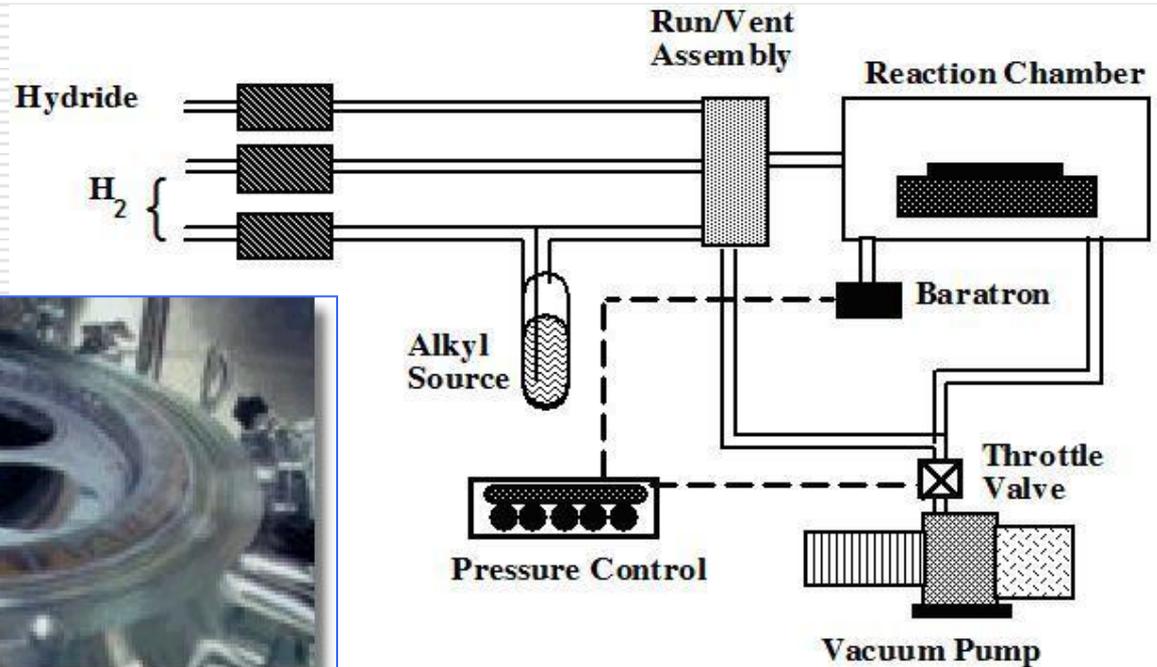




Core Technology

MOCVD (有機金屬氣相沉積法)

- Metal Organic Chemical Vapor Deposition





Core Technology

Production
Reactor

MOCVD Metal Organic Chemical Vapor Deposition

Way to
Produce

Through the organic metal chemical vapor deposition method, the semiconductor film is grown on the substrate, and the epitaxial layer is accurately controlled through the real-time monitoring of the machine to complete the production of epitaxial wafers for different products such as GaAs、InP and GaN.

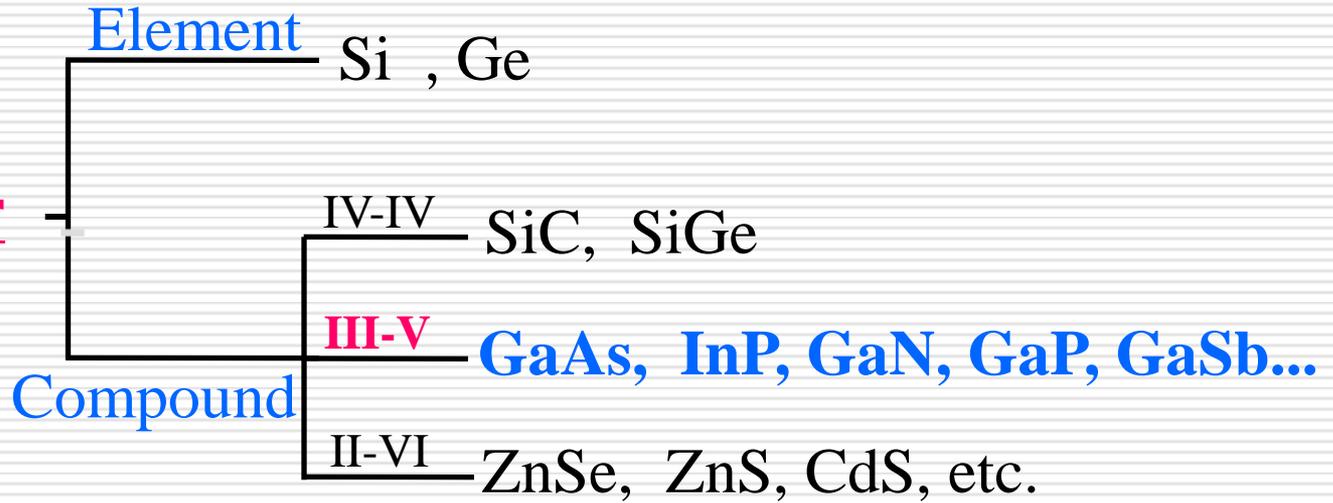
Production
Principle

The epitaxial layer is heated by MOCVD in the cavity of the substrate, and an atomic layer is stacked layer by layer to form an epitaxial layer.



Semiconductor (by Material)

Semiconductor



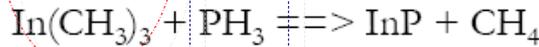
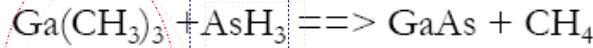
Period	Column II	III	IV	V	VI
2	Be 鈹 Beryllium	B 硼 Boron	C 碳 Carbon	N 氮 Nitrogen	O 氧 Oxygen
3	Mg 鎂 Magnesium	Al 鋁 Aluminum	Si 矽 Silicon	P 磷 Phosphorus	S 硫 Sulfur
4	Zn 鋅 Zinc	Ga 鎵 Gallium	Ge 鍺 Germanium	As 砷 Arsenic	Se 硒 Selenium
5	Cd 鎘 Cadmium	In 銦 Indium	Sn 錫 Tin	Sb 銻 Antimony	Te 碲 Tellurium
6	Hg 汞 Mercury	Tl 鉍 Thallium	Pb 鉛 Lead		

- 二元化合物 Binary : GaAs, InP, GaP, GaN, etc.
- 三元化合物 Ternary : InGaAs, InGaP, AlGaAs, etc.
- 四元化合物 Quaternary : AlGaInP, InGaAsP, etc.
- 五元化合物 Pentanary : AlGaInAsN, etc.



Chemical Reaction During Epitaxy

化學反應式：



主要原物料：

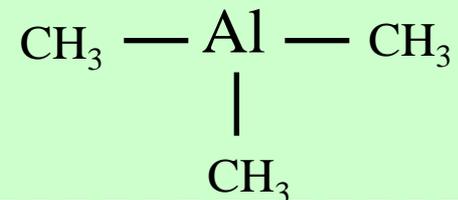
MO Source + **Hydride** + Carrier Gas : **H₂**

- TEAl : Tri-ethyl-Aluminum (C₂H₅)₃Al
- TMGa : Tri-Methyl-Gallium (CH₃)₃ Ga
- TMIn : Tri-Methyl-Indium (CH₃)₃In
- DETe : Di-ethyl-Tellurium (C₂H₅)₂Te
- DEZn : Di-ethyl-Zinc (C₂H₅)₂Zn
- CP₂Mg : Bis (cyclo-penta-dienyl) Magnesium 環戊二烯鎂

- AsH₃ : Arsine
- PH₃ : Phosphine
- SiH₄ : Silane
- Si₂H₆ : Disilane
- H₂Se : Hydrogen Selenide
- CBr₄ : Carbon Tetrabromide

TMAI Tri - Methyl - Aluminum (CH₃)₃Al

三 甲 基 鋁





Advantages of Compound Semiconductor

1. High Electron Mobility 高電子移動速率 (5.7x higher than CMOS)
2. High Frequency Response 高頻率響應
3. Wide Band Width 寬幅之頻寬
4. High Linearity 高線性度
5. High Power 高功率
6. Alternative Choice of Material 材料選擇多元性
7. 抗輻射

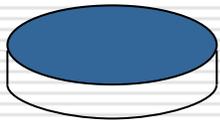
適用於無線通訊、光通訊、雷射



GaAs in Wireless Communication Supply Chain

Sumitomo, Freiberg, AXT

2~6 "GaAs Substrate

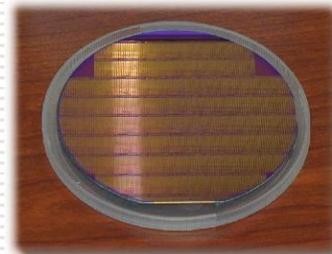


GaAs Epi- Wafer
磊晶片



IDM : Qorvo, Avago,
Skyworks

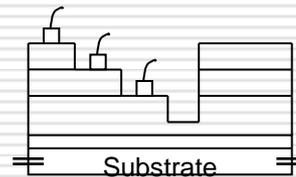
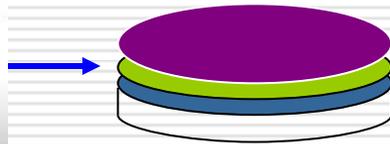
Microelectronics
IC Process



Wireless
Communication



MOCVD Reactor



Foundry :

WIN, AWSC,
GCS



IC Package & Testing



2019-2022Q1 Financial Result

	2022Q1	%	2021	%	2020	%	2019	%
Revenue	839,197	100.00%	3,608,521	100.00%	2,645,003	100.00%	2,530,909	100.00%
Gross margin	363,138	43.27%	1,519,713	42.11%	1,114,404	42.13%	1,034,272	40.87%
Operating Profit	244,584	29.15%	1,056,519	29.28%	687,515	25.99%	648,983	25.64%
Financial Income	27,843	3.32%	-3,842	-0.11%	-40,212	-1.52%	-20,380	-0.81%
Tax	-54,946	-6.55%	-197,596	-5.48%	-114,715	-4.34%	-114,278	-4.52%
Net income	217,481	25.92%	855,081	23.70%	532,588	20.14%	514,325	20.32%
EPS	1.18		4.62		2.88		2.79	



2022 Outlook-Microelectronics

5G Mobile Penetration



WiFi6 / 6E



IoT Smart Link



**Micro
Electronics**

V2X PA



LEO Satellite



5G Base Station



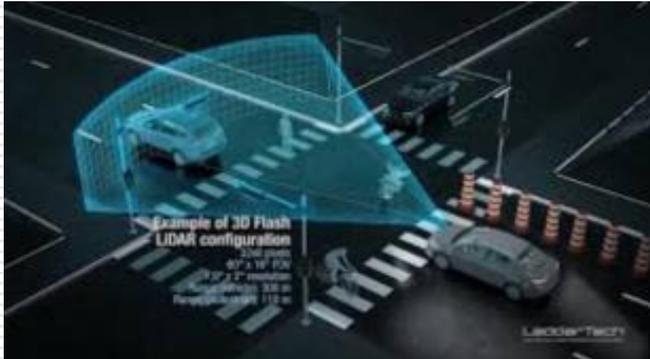
Military





2022 Outlook-Optoelectronics

Car LiDAR



AR / VR Sensing



Opto
electron
ics

Robot Vacuum Sense



Special Heat/IR Imaging



AR / VR

Emitter: VCSEL
Detector: PD
Eye-safety

Wireless

HBT (PA)
pHEMT (Switch/LNA)
WiFi 6/6E/7

VPEC Proprietary and Confidential



LiDAR Turnkey Solution

Emitter: VCSEL, EEL
Detector: PD, APD
Eye-safety (1400nm ~ 1600nm)
Long Range Detection (400m)

V2X

HBT (PA)
pHEMT (Switch/LNA)
WiFi 6/6E/7

